

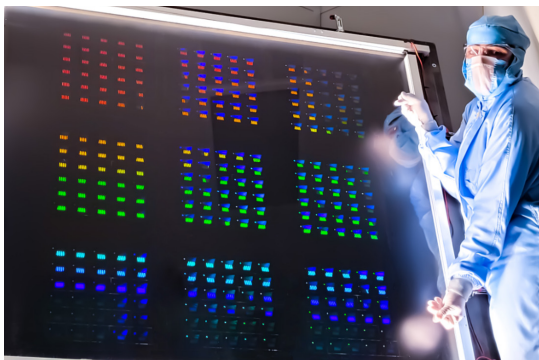
Portis 1100 Platform

Ultimate Modular Flexibility



Watch our Portis platform in action

Portis 1100 is a high-performance Roll-to-Plate (R2P) nanoimprint platform built for advanced R&D, process development, and manufacturing. Its large-area capability, modular architecture, and fully expandable design make it ideal for a wide range of applications.



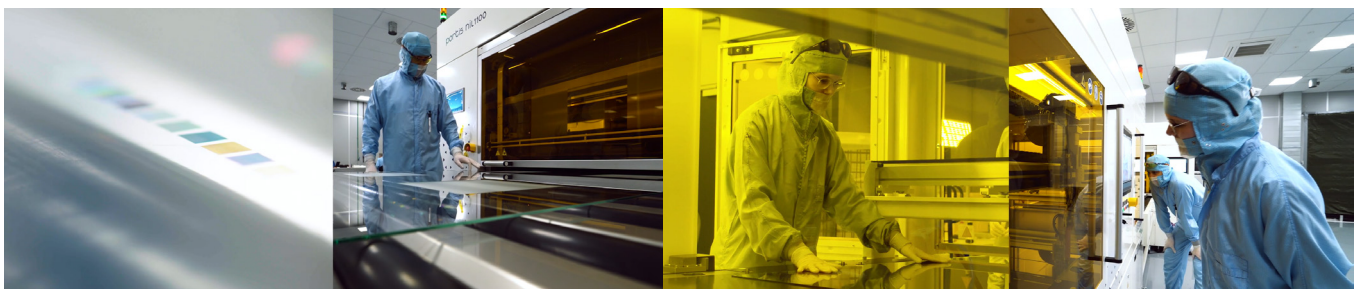
Substrate Size	Up to Gen5 (1100 x 1300 mm ²)
Substrate Thickness	0.5 – 10 mm
Substrate materials	Rigid & flexible (glass, polymer, metal)
Structures	From 50 nm up to 500 μ m
TAKT time	<5 min possible
Wide viscosity range (5-1500 mPas) using Coater C100	
Programmable & accurate spray coating using Primer P100	

High Quality Imprints at Scale

Portis 1100 delivers thin residual layers, air-exclusion imprinting with high-viscosity materials. It provides excellent lateral dimensional stability, and broad compatibility with pre-treatment and post-processing technologies. This flexibility ensures both R&D experimentation and production-grade throughput on a single scalable platform.

Built for Consistency, Scalability, and Reliability

Each Portis module operates fully automatically to ensure stable, repeatable results. Substrate loading, unloading, and module movement are handled manually, providing controlled interaction where needed. With its standalone and flexible design, Portis 1100 can be easily reconfigured, modules can be added, upgraded, or rearranged as production needs evolve.



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